

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1261	yang-seung-man-.in. yang-s-m-.in. yi-ki-ra-.in. yi-k-r-.in. park-yong-hak-.in. park-y-h-.in. kim-sarah-.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/12 09:40
L2	8	yang-seung-man-.in. yang-s-m-.in. yi-ki-ra-.in. yi-k-r-.in. park-yong-hak-.in. park-y-h-.in. kim-sarah-.in.	US-PGPUB; USPAT	OR	ON	2005/12/12 09:44
L4	677	colloidal near2 crystal	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:45
L5	52063	photopolymer\$8 photo-polymer\$8 photo adj polymer\$8	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:45
L6	3241391	interstice space gap vacancy	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:45
L7	3	L4 same L5 same L6	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:50
L8	35	L4 and L5 and L6	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:46
L9	39324	interstitial	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:46
L10	0	L4 same L5 same L9	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:46
L11	6	L4 and L5 and L9	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:51
L12	35	L4 and L5 and L6	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:51
L13	6	L4 and L5 and L9	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:00

L14	0	L13 not L12	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:46
L15	123947	colloidal	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:46
L16	2	(L9 L6) with L15 with L5	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:00
L17	853	(L9 L6) with L15	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:47
L18	2	(L9 L6) with L15 with L5	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:00
L19	2	L17 same L18	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:01
L20	4	(L9 L6) same L15 same L5	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:01
L21	373504	photosensitive photo-sensitive (sensitive near (photo radiation energy light))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:47
L22	22868	monomer near2 solution	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:47
L23	26	L21 near3 L22	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:02
L24	0	L15 same L23	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:47
L25	1	L15 and L23	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:02

L27	2281481	polymer\$8	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:47
L28	14825	L21 near3 L27	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:47
L29	144	L22 with (L6 L9)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:47
L30	0	L28 same L29	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:47
L31	2	L28 and L29	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:03
L32	178099	colloid\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:48
L33	9	(L5 L28) same L32 same (L6 L9)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:03
L34	3362741	L6 L9 void	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:48
L35	715710	suspension silicia	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:48
L36	245	L34 same (L35 L32) same (acrylate methacrylate)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:48
L37	20	L36 same (L5 L21 light radiation energy mask photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:04
L38	35889	L34 same (L35 L32)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:48

L39	55	L38 same (L5 L21 light radiation energy mask photomask) same monomer\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:04
L40	0	("2004/0146811").URPN.	USPAT	OR	ON	2005/12/12 09:48
L41	35	("2822272"   "2871119"   "3100150"   "3111407"   "3382069"   "3661589"   "3681066"   "3733200"   "3765894"   "3787208").PN. OR ("4522910").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/12/12 10:06
L42	24	("3776754").PN. OR ("4188449").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/12/12 10:06
L43	18	(methacrylate acrylate) same ((L6 L9) with L32)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:06
L44	45	(monomer) same ((L6 L9) with L32)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:07
L45	6	(("5332651") or ("5994033") or ("20020143073")).PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/12/12 09:49
L46	3	L45 and (acrylate methacrylate polyacrylate polymethacrylate)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:49
L47	1265	L5 near3 (second! additional\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 09:50
L48	4	L47 with L32	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:07
L49	8	L47 same L32	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/12/12 10:16
L50	1	(4 same 5 same monomer).clm.	US-PGPUB	OR	ON	2005/12/12 10:18
L51	3	(colloidal same 5 same monomer).clm.	US-PGPUB	OR	ON	2005/12/12 10:19
L53	6	(colloidal same polymeriz\$5 same monomer same (irradiat\$5 expos\$5 light radiation uv)).clm.	US-PGPUB	OR	ON	2005/12/12 10:21
L54	0	(colloidal same polymeriz\$5 same monomer same (photomask mask)).clm.	US-PGPUB	OR	ON	2005/12/12 10:21

L55	1	(colloidal same 5 same monomer same (photomask mask)).clm.	US-PGPUB	OR	ON	2005/12/12 10:21
L56	1	(colloidal same 5 same (photomask mask)).clm.	US-PGPUB	OR	ON	2005/12/12 10:21